## Achieving electrical connections to (sub-)micrometer size vertical transport structures based on GaN

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In order to verify experimentally theoretical prediction about large spin filtering capabilities of thin ferromagnetic (Ga,Mn)N layers, devices as GaN:Si/(Ga,Mn)N/GaN:Si were grown on sapphire substrates for vertical transport studies [1]. It was found that both 200 x 200 and 60 x 60  $\mu$ m mesas, despite exhibiting some increasing on lowering temperature non-ohmic behavior [1], were generally shorted by highly conductive sapphire-GaN misfit-related threading dislocations (TDD) [2]. In order to mitigate the detrimental influence of the TDD on the vertical transport through (Ga,Mn)N magnetic barriers a reduction of the mesas area to such a degree is required that, statistically, at least one-in-four devices should be TDD free. For a typical aerial density of TDD approaching  $10^{10}$  cm<sup>-2</sup> structures smaller than 0.5  $\mu$ m are envisaged. However, to electrically connect such small devices with the experimental set up, special conductive suspended structures - the air bridges – have to be fabricated, as sketched in Fig. 1a.

Here, in order to achieve this goal, that is to elaborate the whole technological process, the first 12  $\mu$ m long and 200 nm narrow gold air bridges with 6-7  $\mu$ m pad sizes have been successfully fabricated by electron beam aided lithography and electrically tested. We find them to be both mechanically and electrically robust with electrical resistance of about 50  $\Omega$ . This technological effort is the first step towards elaboration of fully operational sub-micrometer devices.

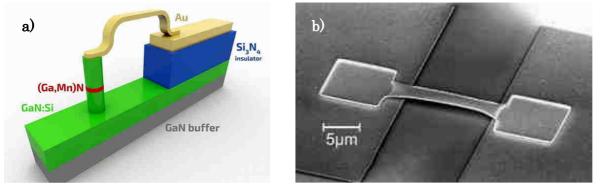


Fig. 1: a). Schematic representation of the (sub-)micro-meter size vertical mesa connected to a contact pad by an "air-bridge"; b). SEM photo of the gold "air bridge" connector.

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[1] K. Kalbarczyk, M. Foltyn, M. Grzybowski, W. Stefanowicz, R. Adhikari, Tian Li, R. Kruszka, E. Kaminska, A. Piotrowska, A. Bonanni, T. Dietl, M. Sawicki, Acta Phys. Polon. **130**, 1196 (2016).

[2] P. Kozodoy, J.P. Ibbetson, H. Marchand, P.T. Fini, S. Keller, J.S. Speck, S.P. DenBaars, U.K. Mishra, Appl. Phys. Lett. **73**, 975 (1998).